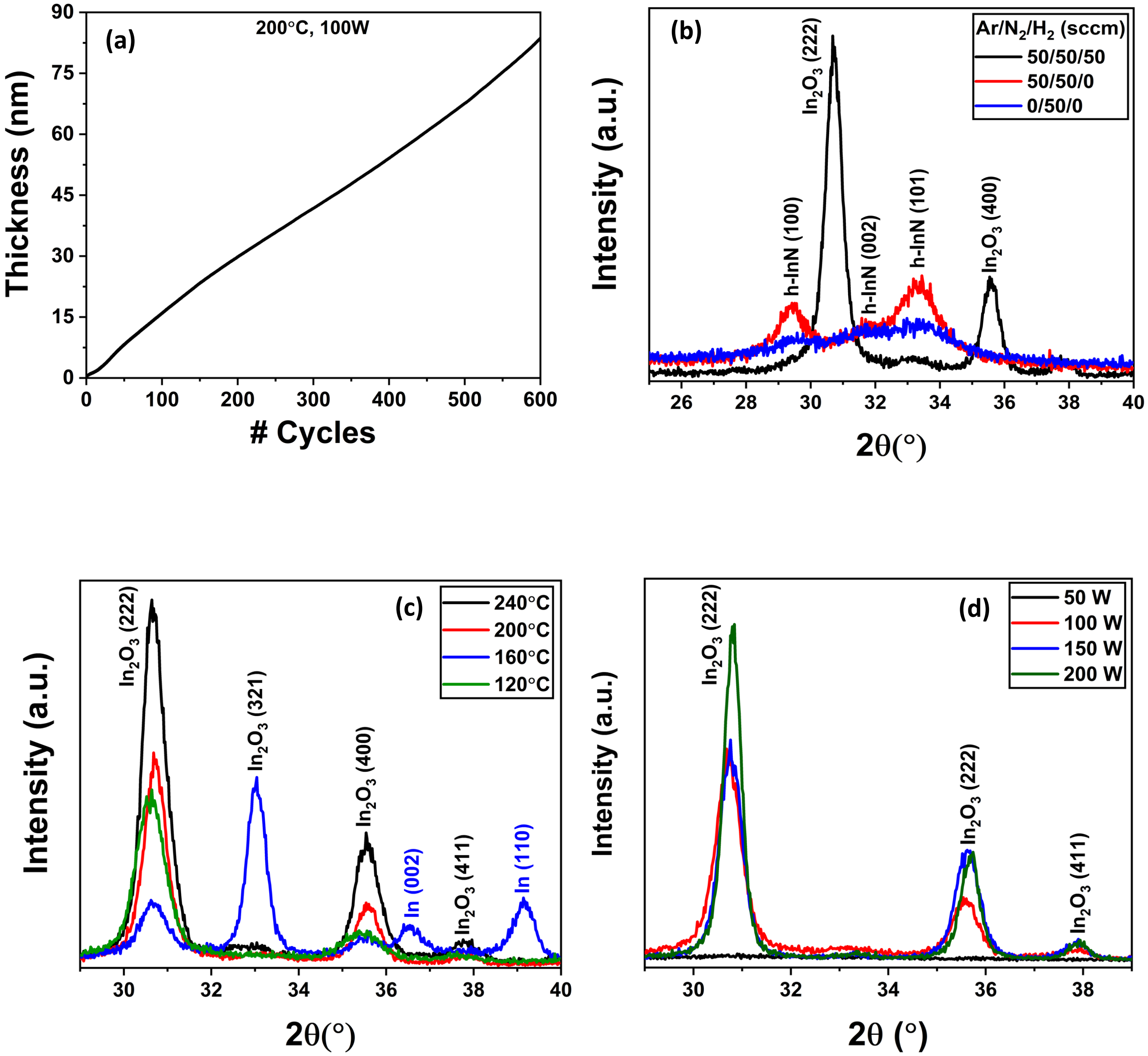

Figure 1. (a) 600-cycle linearity curve of TMI interaction with Ar/N$_2$-plasma in HCPA-ALD recorded via real-time *in-situ* ellipsometry. (b) GIXRD spectra of plasma composition dependence on the 600-cycles grown films at 100 W and 200 °C. (c) GIXRD scan of the films grown with 50/50/50 sccm plasma mixture with varying substrate temperatures at 100 W. (d) GIXRD spectra of the films deposited at different RF-plasma powers and 200 °C.